13.5nm, 25.4mm Dia, 5° AOI, EUV Spherical Mirror

TECHSPEC® Extreme Ultraviolet (EUV) Spherical Mirrors

Stock **#11-730**   **20+ In Stock**

‒ 1 ＋   **€4.310**.⁰⁰

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Qty 1+	**€4.310,00** each
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General

Type:	
Spherical Mirror	

Physical & Mechanical Properties

Diameter (mm):	
25.40 +0.00/-0.13	
Thickness (mm):	
6.35 ±0.25	
Surface Roughness (□):	

<3 RMS

Optical Properties

Coating Type:	
Metal/Semiconductor	
Coating:	
Mo/Si Multilayer Top Layer: Silicon	
Surface Flatness (P-V):	
λ/10 @ 632.8nm	
Design Wavelength DWL (nm):	
13.5	
Effective Focal Length EFL (mm):	
250.00	
Substrate: ▢	
[Fused Silica](#) (Corning 7980)	
Angle of Incidence (°):	
5	
Coating Specification:	
R_{abs} >60% @ 13.5nm	
Radius R_1 (mm):	
500.00	
Radius of Curvature (mm):	
500.00	
Full Width-Half Max FWHM (nm):	
0.50	

Regulatory Compliance

Certificate of Conformance:	
View	

Product Details

- Mo/Si Multilayer Coating on Super-Polished Substrates
- Maximum Achievable Reflection at 13.5nm
- Designed for EUV Beam Focusing Applications
- Narrow Pass Band for HHG Applications

Extreme Ultraviolet (EUV) Spherical Mirrors feature a multilayer Mo/Si coating providing greater than 60% reflection at 13.5nm. They are designed for a 5° angle of incidence and intended for focusing unpolarized EUV laser sources. A surface roughness of less than 3▢ RMS minimizes scatter. This is essential for EUV wavelengths which experience more scattering than longer wavelengths. EUV Spherical Mirrors have a very narrow pass band of approximately 0.5nm, ensuring that only the 13.5nm harmonic of interest is reflected in high harmonic generation (HHG) applications. **Typical applications** for EUV spherical mirrors include Coherent Diffractive Imaging (CDI), EUV imaging, and EUV nanomachining.

Note: Test data from each mirror's production run sample included.

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